

AZ nLOF 2020 – run sheet

Merck

[nanyte.com/photorelists/az-nlof-2020](https://www.merck.com/photorelists/az-nlof-2020) · last updated 2026-07-26

Thickness: 1.6–4.6 μm

Softbake: 110 °C (100–110 °C) · 60 s · hotplate

Exposure dose: 66 mJ/cm² @ 365 nm

Post-exposure bake: 110 °C (100–115 °C) · 60 s

Develop: Developer AZ 300MIF · Dilution undiluted (ready-to-use 0.26N / 2.38% TMAH developer; no dilution ratio stated) · Time 60 s · Method puddle